

REMARKS

Favorable reconsideration is respectfully requested.

The claims are 1 to 39.

Claims 1 to 39 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Subramanian et al. (U.S. 6,127,089) in view of Zampini et al. (U.S. 6,503,689) and in further view of Matsumoto et al. (JP 1-217328) in view of its English language abstract.

This rejection is respectfully traversed.

1. Further to the rejection in the previous Official Action, the present rejection additionally cites Matsumoto et al. The rejection points out that: "Matsumoto et al. disclose a resin for optical use comprising a methacrylate polymer having a sulfonic acid residue. The inclusion of this polymer into a resin increases the optical effect and strength of a material."

2. As described in the English abstract thereof, the compound of Matsumoto is a pi-electron conjugated compound having a cation in the molecule, which is dispersed into an ionic polymer. Matsumoto refers to a polymer containing sulfonic acid residue as an example of the ionic polymer. According to Matsumoto, the compound may give a nonlinear optical material having an extremely great tertiary nonlinear optical effect.

3. A nonlinear optical material having a tertiary nonlinear optical effect is usually used for optically bistable devices. Such material is never intended to be dissolved in any liquid upon use. Thus, the compound of Matsumoto has no technical relationship with the material to be washed off of the present invention.

4. Although Applicants have thoroughly examined the Matsumoto reference, there is, of course, no disclosure regarding a resin material to be washed off upon use.

5. As pointed out in response to the previous Action, the layer made of the presently claimed material is capable of being washed off together with a patterned photoresist layer by applying a solution for removing the photoresist layer, which is a significant advantage as an undercoating layer or a filler material in the manufacture of wiring pattern.

Even if Matsumoto discloses a polymer containing similar group to that of the claimed material, it is totally impossible for one skilled in the art to arrive at the presently claimed material on the basis of the disclosure of Matsumoto with other cited references, because Matsumoto reference includes no disclosure regarding a material to be washed off in a wiring formation process.

For the foregoing reasons, the rejection on prior art is untenable and should be withdrawn.

No further issues remaining, allowance of this application is respectfully requested.

If the Examiner has any comments or proposals for expediting prosecution, please contact undersigned at the telephone number below.

Respectfully submitted,

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December 7, 2005